

# WEST Search History

DATE: Thursday, April 03, 2003

**Set Name Query**  
side by side

**Hit Count Set Name**  
result set

*DB=USPT,JPAB,EPAB,DWPI; PLUR=YES; OP=ADJ*

L24	L20 same ((wafer or semiconductor) with (clean\$ or rins\$3))	29	L24
L23	L20 same ((substrate or wafer or semiconductor) with (clean\$ or rins\$3))	30	L23
L22	L20 and ((substrate or wafer or semiconductor) with (clean\$ or rins\$3))	103	L22
L21	L20 with ((substrate) (clean\$ or rins\$3))	0	L21
L20	(methylpyrrolidinone)	2585	L20
L19	L16 and (acetic acid with methylpyrrolidinone)	0	L19
L18	L16 and (acetic acid with methylpyrrolidinone)	0	L18
L17	L16 with acetic acid with methylpyrrolidinone	0	L17
L16	remov\$3 with etch\$3 residue	685	L16
L15	L14 and methylpyrrolidinone	0	L15
L14	5863344.pn.	2	L14
L13	6863344.pn.	0	L13
L12	6136767.pn.	2	L12
L11	6, 136767.pn.	0	L11
L10	otten-l\$.in.	30	L10
L9	Eisemann-D\$.in.	0	L9
L8	Eisemann-D.in.	0	L8
L7	l1 and dry\$3	1	L7
L6	Eisenmann-D\$.in.	3	L6
L5	l1 and dry\$3	1	L5
L4	l1 and corros\$4	1	L4
L3	l1 and corrosion	1	L3
L2	L1 and (hydroxylamine or methylpyrrolidinone)	0	L2
L1	6313048.pn.	2	L1

END OF SEARCH HISTORY